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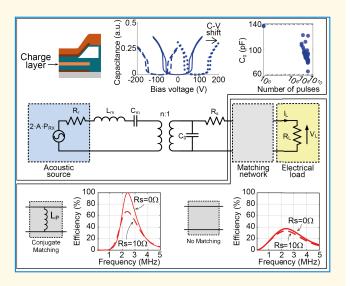
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# Pre-Charged Collapse-Mode Capacitive Micromachined Ultrasonic Transducer (CMUT) Receivers for Efficient Power Transfer

Marta Saccher<sup>®</sup>, *Member, IEEE*, Alessandro Stuart Savoia<sup>®</sup>, *Member, IEEE*, Rob van Schaijk, Johan H. Klootwijk, *Senior Member, IEEE*, and Ronald Dekker

**Abstract**—Capacitive micromachined ultrasonic transducers (CMUTs) offer several advantages over standard lead zirconate titanate (PZT) transducers, particularly for implantable devices. To eliminate their typical need for an external bias voltage, we embedded a charge storage layer in the dielectric. The objective of this study was to evaluate the performance of plasma-enhanced chemical vapor deposition (PECVD) Si<sub>3</sub>N<sub>4</sub> and atomic layer deposition (ALD) Al<sub>2</sub>O<sub>3</sub> as materials for the charge storage layer and two different dielectric layer thicknesses, focusing on their application as receivers in a wireless power transfer link. Capacitance-voltage (CV) measurements revealed that Si<sub>3</sub>N<sub>4</sub> has a higher charge storage capacity compared to Al<sub>2</sub>O<sub>3</sub>. Additionally, a thicker dielectric layer between the bottom electrode and the charge storage layer  $(B_{diel})$  improved both charge trapping and retention, as assessed in dynamic accelerated lifetime transmit (TX)-mode tests. We then analyzed the power conversion performance of the fabricated CMUTs through both simulations and experiments. We performed extensive modeling based on an equivalent circuit derived from



electrical impedance measurements of the fabricated CMUTs. The model was used to predict the power conversion efficiency under various conditions, including the charging field strength, the operating frequency, and parasitic series resistance. Power transfer experiments at 1- and 2.4-MHz recorded efficiencies exceeding 80% with an optimally matched load and up to 54% with a purely resistive load. Results confirmed that, with optimal load matching, the efficiency of different CMUT variants is comparable, indicating that the optimal variant should be selected based on additional criteria, such as charge retention time.

*Index Terms*— Capacitive micromachined ultrasonic transducers (CMUTs), implantable medical devices (IMDs), pre-charged CMUT, ultrasonic power transfer, zero-bias transducers.

# I. INTRODUCTION

N RECENT years, new ultrasound markets have emerged to meet new customer demands, including continuous organ monitoring and handheld systems connectable to smartphones. Ultrasound transducers are now also considered as wireless power receivers for implantable medical devices (IMDs). However, traditional manufacturing processes, such as those using lead zirconate titanate (PZT) ultrasound transducers, have high manual labor costs and use toxic metals, limiting their suitability for certain applications.

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An ultrasonically powered IMD platform includes a transmit (TX) transducer, medium, receive (RX) transducer, power management unit (PMU), and load. When designing an ultrasonically powered IMD, several critical factors must be considered. Key among these are the size of the device—particularly the RX size—the energy efficiency of the IMD, the RX sensitivity and bandwidth, and the biocompatibility and reliability [1].

The efficiency of the platform is crucial because low IMD efficiency requires transmitting higher power into the surrounding medium, which increases the risk of tissue damage. The overall efficiency of the IMD depends on the combined efficiencies of its components, especially the acoustic-to-electrical power conversion efficiency of the RX. Most research on ultrasonically powered IMDs still uses PZT crystals for the RX transducers, due to their efficiency ranging up to 60% [2], [3], [4], [5], [6], [7], thanks to

# **Highlights**

- Performance characterization of bias-free pre-charged collapse-mode CMUTs for power transfer applications obtained by embedding a charge storage layer (Si<sub>3</sub>N<sub>4</sub> or Al<sub>2</sub>O<sub>3</sub>) in the dielectric.
- All tested charging electric fields produced collapse-mode devices showing promising charge retention, with power transfer simulations and experiments aligning and achieving more than 80% efficiency.
- Their CMOS compatibility and lack of external bias enable their use in implantable devices, imaging probes, patches, point-of-care devices, and ultrasound catheters, among others.

their high electromechanical coupling coefficient [8], [9]. Micromachined ultrasonic transducers (MUTs), such as piezo-electric MUTs (PMUTs) and capacitive MUTs (CMUTs), are alternatives to PZT transducers. PMUTs use a thin-film piezoelectric layer, while CMUTs use electrostatic actuation. MUTs have larger bandwidths, are CMOS-compatible, and can be made biocompatible and miniaturized, addressing several key considerations in the design of ultrasonically powered IMDs. Recently, a few studies investigated the use of PMUTs as RX transducers in IMDs. However, the reported results show that they all suffer from low efficiency, due to their small electromechanical coupling coefficient [10], [11], [12], [13], [14].

In this article, we used CMUTs as RX. A CMUT consists of a membrane suspended over a vacuum gap. Through the vibration of this membrane, electrostatically actuated with an opposing electrode beneath the vacuum gap, ultrasound can be transmitted into, or received from the medium coupled to the membrane. CMUTs require an external dc bias voltage ranging between 50 and 100 V to bring the top membrane closer (noncollapse mode) or in partial contact (collapse mode) to the bottom dielectric. In addition, collapse mode operation increases the TX and RX sensitivity, and the output pressure up to three times compared to non-collapse mode [15], [16]. However, the need for an externally applied dc bias requires additional circuitry and limits miniaturizability. Moreover, the use of high voltages is not desirable for medical applications. To eliminate the need for an external bias voltage, special types of CMUTs can be fabricated with a charge-trapping layer embedded in their dielectric layer stack. By trapping enough charge, the device can be operated in collapse mode without the need for a dc bias. The concept of dielectric charging is not new; however, only a few groups investigated this concept applied to CMUTs [16], [17], [18], [19], [20], [21]. Dielectric charging, in fact, is usually seen as a reliability issue in MEMS devices since it causes instability of the device characteristics up to the point at which the device fails [22], [23], [24], [25]. The few groups that investigated pre-charged CMUTs, used SiO<sub>2</sub> or Si<sub>3</sub>N<sub>4</sub> as material for the charging layer. However, most of them produced non-collapse-mode CMUTs, with the exception of Ho et al. [17], who used a low-frequency CMUT operating at 140 kHz. Choi et al. [20] compared the performance of Si<sub>3</sub>N<sub>4</sub>-SiO<sub>2</sub> and SiO<sub>2</sub> as charging layers, concluding that Si<sub>3</sub>N<sub>4</sub> maintains its performance for a longer duration due to superior charge retention. It is evident from these studies that trapping sufficient charge to

achieve a pre-charged collapse-mode CMUT is challenging, and the choice of material for the charge-trapping layer is crucial. Leveraging the fundamental concept of dielectric charging from the semiconductor memory industry, materials employed in this domain can be integrated into the CMUT dielectric as a charge storage layer to develop stable precharged collapse-mode CMUTs. In recent years, we conducted preliminary experiments with a high-frequency CMUT array (8-MHz center frequency) originally designed for imaging applications, incorporating an Al<sub>2</sub>O<sub>3</sub> charge-trapping layer in its dielectric. The experiments demonstrated that these devices can trap a sufficient amount of charge to maintain collapse mode and deliver excellent acoustic performance and power conversion efficiency [26], [27]. We successfully used this array to create a B-mode image without the need for an external bias, utilizing a purely ac driving signal [28]. These promising results motivated us to develop a second generation of prechargeable CMUTs, designed for wireless power transfer at a lower frequency range.

The primary objective of this article is to investigate precharged collapse-mode CMUTs evaluating their performance and their suitability as candidates for replacing standard externally biased CMUTs or other ultrasonic transducers with a focus on their application as ultrasound receivers in IMDs. To achieve this, we evaluated the performance of plasma-enhanced chemical vapor deposition (PECVD) Si<sub>3</sub>N<sub>4</sub> and atomic layer deposition (ALD) Al<sub>2</sub>O<sub>3</sub> as materials for the charge storage layer in the dielectric of pre-charged collapse-mode CMUTs. Preliminary findings comparing the performance of Si<sub>3</sub>N<sub>4</sub> and Al<sub>2</sub>O<sub>3</sub> in terms of charge trapping, static charge retention, and acoustic-to-electric power conversion efficiency were presented in [29]. In this article, we expand on our previous work by examining the impact of varying thicknesses of the insulating layer beneath the charge storage layer and by analyzing charge retention in TX mode under different experimental conditions. In addition, in this work, we analyzed their power conversion performance both through simulations and experiments. Simulations were performed using an equivalent circuit model derived from the electrical impedance measurements of single-element precharged CMUT prototypes. These simulations quantified their efficiency using an optimal load under various operating frequencies, charging electric fields, and with or without matching networks. We considered both ideal conditions and nonideal characteristics, such as the presence of parasitic elements including the resistance introduced by electrical

interconnections on the chip. We conducted power conversion experiments on the fabricated prototypes to evaluate their efficiency. We then analyzed and discussed the simulation and measurement results to quantitatively assess the performance, correlating them with the practical aspects considered in this study.

# II. MATERIALS AND METHODS

# A. CMUT Fabrication

The collapse-mode CMUTs used in this work were designed and fabricated with the aim to be used as ultrasonic power receivers. The microfabrication technology is based on a sixmask, low-temperature (<400 °C) sacrificial release process that uses CMOS-compatible materials. These CMUTs were designed for a two-way center frequency in immersion around 3 MHz and have a membrane diameter of 355  $\mu$ m. The fabricated CMUTs consist of 173 membranes connected in parallel, occupying an area of  $5 \times 5 \text{ mm}^2$ . Typically, these CMUTs are operated in collapse mode with a bias voltage of 120 V, significantly above the collapse voltage of  $\approx$ 70 V. However, such a high dc bias cannot be used for power transfer in implantable devices. We, therefore, changed the standard CMUT architecture to eliminate the need for a bias voltage by replacing the bottom dielectric layer consisting only of SiO<sub>2</sub> with a stack including a charge storage layer.

The fabrication process of the CMUT begins with a silicon wafer provided with a PECVD oxide dielectric layer. Alternatively, an application-specified integrated circuit (ASIC) wafer with integrated electronics can be used. The bottom electrode, made of an aluminum alloy, is then deposited and patterned on top of the oxide layer [Fig. 1(a.i)]. Next, the charge storage layer (200-nm Al<sub>2</sub>O<sub>3</sub> or Si<sub>3</sub>N<sub>4</sub>) is deposited on top of the bottom electrode sandwiched between two SiO<sub>2</sub> layers (120 or 200 nm below, and 60 nm above the charge storage layer). Subsequently, a sacrificial metal layer made of an aluminum alloy (mask 2) is deposited and patterned, which will later be removed by etching to create the vacuum-sealed cavity of the CMUT [Fig. 1(a.ii)]. A second dielectric layer (60-nm SiO<sub>2</sub>) is deposited, followed by the deposition and patterning of the top electrode (mask 3) [Fig. 1(a.iii)]. The first part of the CMUT membrane (6-\mu Si<sub>3</sub>N<sub>4</sub>) is then deposited [Fig. 1(a.iv)]. An etch hole is patterned on the side of the membrane (mask 4) to etch the sacrificial material and form the cavity [Fig. 1(a.v)]. This etch hole is then sealed by depositing the second part of the membrane in a low-pressure environment, creating the vacuum-sealed cavity [Fig. 1(a.vi)]. The total thickness of the  $Si_3N_4$  membrane is 9  $\mu$ m. The CMUT processing is completed by etching vias (mask 5) and patterning bond pads (mask 6) for contacting the top and bottom electrodes. Scanning electron micrograph (SEM) photographs and a schematic cross section of the fabricated devices showing different layers are shown in Fig. 1(b)–(d).

We designed and fabricated four-layer stack variants. Two variants were fabricated with ALD-deposited Al<sub>2</sub>O<sub>3</sub> as the charge storage layer, and the other two with PECVD-deposited Si<sub>3</sub>N<sub>4</sub>. For each charge storage layer material, two different thicknesses of the SiO<sub>2</sub> dielectric layer in contact with the

bottom electrode ( $B_{\rm diel}$ ) were used: one variant with a thickness of 120 nm, and the other with a thickness of 200 nm. Fig. 1(e) provides an overview of these variants, along with their respective names as referenced throughout this article.

To evaluate the dielectric breakdown of the CMUTs, we fabricated metal-insulator-metal (MIM) capacitors with dimensions of size  $300 \times 300~\mu\text{m}^2$ . MIM capacitors are structurally simpler yet effectively emulate the pull-in state of CMUTs. We included them in the mask design of the CMUTs; therefore, they have the same dielectric stack as they are exposed to the same processing steps. Accurate measurement of the breakdown field requires a known electrically active area, which is difficult to estimate for collapsed CMUTs because it changes continuously during a voltage sweep, making precise measurement almost impossible. In contrast, MIM capacitors have a predefined and stable area, simplifying breakdown field measurement and providing a reliable means of estimating the breakdown field for CMUTs.

# B. I-V and CV Measurements

To determine the breakdown voltage of the MIM capacitors, we measured their current-voltage (I-V) curves. We used a Keithley 237 High Voltage Source/Measure Unit (Keithley Instruments, Cleveland, OH, USA), and linearly swept the voltage from 0 V until breakdown, with 1-V increments. We set the compliance current to 5 mA.

To minimize any alteration of the stored charge in our device, we employed a fast capacitance–voltage (CV) protocol with a voltage sweep rate of 80 V/ms. We superimposed a small ac signal of 81 MHz on a 200-Hz triangular wave varying between 0 and  $\pm 200$  V. We used the change in the phase of the impedance when the CMUT goes in and out of collapse to draw the CV curve. Additionally, to further limit any change in the charge within the dielectric, we used two measurement protocols: a dc bipolar sweep between positive and negative voltages for uncharged devices, and a dc unipolar sweep of either only positive or negative voltages for devices charged with positive and negative polarities, respectively. We measured three samples for each experimental condition.

# C. CMUT Precharging

In this study, we investigated the effects of charging the CMUT devices with different electric fields on the equivalent built-in voltage, the charge retention, and the power conversion efficiency. We pre-charged the CMUTs by applying electric fields ranging from 7.5 to 8.5 MV/cm, both with positive and negative polarities with respect to the bottom electrode. These parameters were selected based on results from our previous work, where we achieved stable pre-charged CMUTs by applying electric fields within this range [27], [30]. We applied each charging voltage to a pristine device for 5 min, where pristine indicates an uncharged and unmeasured device. In this work, the 5-min duration was selected arbitrarily, and a shorter charging time would still be sufficient to create a pre-charged collapse-mode device.

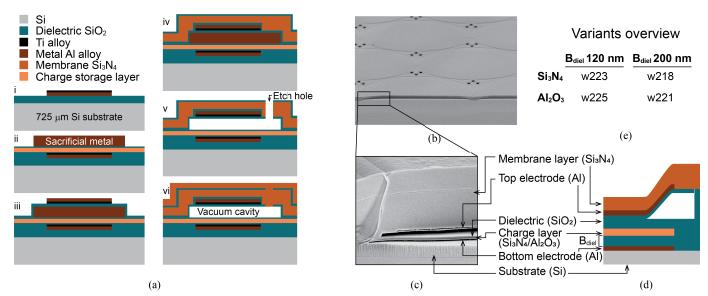


Fig. 1. (a) Schematic process flow of CMUT fabrication. (i) Bottom electrode deposition on top of oxide layer on Si substrate. (ii) Deposition of bottom dielectric layer stack including charge storage layer ( $Si_3N_4$  or  $Al_2O_3$ ), and deposition and patterning of the sacrificial metal. (iii) Deposition of second dielectric layer ( $SiO_2$ ), and deposition and patterning of top electrode. (iv) Deposition of the first part of membrane layer. (v) Patterning of etch hole and removal via etching of the sacrificial metal to form the cavity. (vi) Sealing of the cavity in a low-pressure environment to form the vacuum gap by deposition of the second part of the membrane. The processing is finished with etching vias and patterning of bond pads for contacting top and bottom electrodes. (b) SEM photograph of a cross section of the fabricated CMUTs. (c) Magnification of SEM photograph highlighting the CMUT cell layers. (d) Schematic of the collapse-mode CMUT. (e) Overview of the fabricated variants with their respective names.

# D. Charge Retention

Charge retention over time represents the major challenge for the pre-charged collapse-mode CMUTs, and it depends on the material of the dielectric layer, the deposition method, and the structure of the device. We performed three types of measurements to estimate the retention of the charge stored in the CMUTs. First, a static charge retention test, in which CMUT samples were not actively driven but underwent accelerated lifetime tests (ALTs) using temperature as an accelerating factor. Additionally, two other tests were conducted with the CMUTs operated in TX mode. In these tests, we monitored their impedance and output pressure, respectively, over the number of stimulation pulses. While this article primarily focuses on the use of pre-charged CMUTs in RX mode, we evaluated their performance in TX mode to explore their potential for other applications, such as imaging probes, wearable patches, or intravascular catheters.

1) Static: In these tests, the devices were not operated either in TX or RX mode; therefore, we could estimate the charge retention in conditions such as storage or periods of nonoperation. By performing multiple tests at different temperatures, the retention of the charge stored in the CMUTs can be estimated for the desired temperature (e.g., the body temperature of 37 °C). We used bare die CMUTs, pre-charged them with an electric field of -8 MV/cm for 300 s, and then placed them on a hotplate set at temperatures ranging from 140 °C to 160 °C. We programmed an impedance analyzer (Keysight E4990A, Keysight Technologies, Santa Rosa, CA, USA) to measure the CMUT impedance at regular intervals of time until the device failed. We defined the time to failure as when more than half of the CMUT membranes are out of collapse mode. This was determined using the method described in [27]. We repeated the test at least two times for each experimental condition.

2) Dynamic: For the impedance monitoring tests, we precharged bare die CMUTs with an electric field of -8 MV/cm for 300 s. We immersed them in Fluorinert and monitored their impedance over the number of stimulus pulses by using a Keysight E4990A impedance analyzer. To generate the stimulation pulses, we used a custom-made pulser board set to generate a two-cycle unipolar square wave burst at 2.6 MHz and 50% duty cycle, with a pulse repetition frequency of 100 kHz. We used the value of the equivalent blocked capacitance of the 173 cells composing the CMUTs, extrapolated from the measured impedance, to determine the number of cycles to failure, and we compared it to the value of the equivalent blocked capacitance at pull-in. This value is around 80 pF for all the CMUT variants, and it was used as a threshold to determine the charge retention of the devices. The test was repeated at least two times for each experimental condition.

For the output pressure monitoring tests, we mounted the CMUTs on a printed circuit board (PCB) and coated them with a thin layer of polybutadiene rubber (PBR). We charged them with an electric field of -7.5 MV/cm for 300 s. We then immersed them in a water tank filled with degassed water and centered a needle hydrophone (2762, Precision Acoustics, Dorchester, U.K.) at a distance of 3 mm from the CMUT surface to measure the output pressure. To generate the stimulation pulses, we used the same custom-made pulser board mentioned in the previous paragraph. For this experiment, we used a two-cycle bipolar square wave burst at 2.6 MHz and 50% duty cycle, with a pulse repetition frequency of 100 kHz.

# E. Modeling and Experimental Analysis of Power Conversion

In an ultrasonic wireless power link, several critical elements are involved: the TX system, consisting of the driving

electronics, and an ultrasonic transducer capable of converting electrical power into acoustic power and radiating it into a propagation medium; the propagation medium, introducing attenuation phenomena such as diffraction, scattering, and absorption; and the RX system, comprising an ultrasonic transducer that converts acoustic power into electrical power, and conditioning electronics including circuits for the optimal transfer of the converted power to a load. As this study focuses on evaluating the performance of pre-charged CMUTs as transducer elements within the RX system, we have not considered the generation and propagation aspects of the system in our evaluations since these were extensively covered in existing literature. Our primary focus has been on the conversion of the acoustic power received by the CMUT into electrical power and its subsequent transfer to a load. For simplicity, we have considered a purely resistive linear electrical load and analyzed the conversion efficiency both without impedance matching and with a simple conjugate matching network to maximize power transfer.

Our analysis employed both modeling and experiments. The modeling accounted for the electromechanical characteristics of the pre-charged CMUT transducer, including its actual electrical impedance and the resulting electromechanical coupling, also comprising parasitic elements such as the series resistance of the electrical interconnections. We have conducted simulations to quantify the impact of the operating frequency and the interconnection parasitic resistance on power conversion efficiency, with and without the matching network. We, then, performed experiments on the four CMUT variants under different precharging conditions across a range of frequencies, and with and without the matching network. The simulation and experimental results were then contextually analyzed and discussed, providing a comprehensive understanding of the factors influencing power conversion efficiency in ultrasonic wireless power transfer systems.

1) CMUT Equivalent Circuit Model: To analyze the power conversion from the acoustic domain to the electrical domain, we used the equivalent circuit model of a pre-charged CMUT based on Mason's [31] model, as shown in Fig. 2(a). This model describes the electromechanical transduction through a two-port network comprising an electrical loop and a mechanical loop, coupled via a transformer with a turn ratio of 1:n. The electrical loop includes the blocked capacitance  $(C_0)$ , while the mechanical loop includes the series combination of  $C_m$  and  $L_m$ , representing mechanical compliance and mass, respectively. The voltage in the mechanical loop represents the total force on the transducer surface, while the current represents the average velocity. The equivalent circuit also includes a series resistance  $(R_s)$  in the electrical port, representing the finite resistance of the CMUT's electrical interconnections, and a parallel resistance  $(R_r)$  in the mechanical port, representing the CMUT's radiation impedance. This equivalent circuit accurately represents the vibrating behavior around the fundamental mode of vibration of a spatially periodic layout of CMUT cells electrically connected in parallel and coupled to the propagation medium. It assumes that plane waves are radiated and received, which is valid if the pitch (the center-tocenter distance between adjacent CMUT cells) is smaller than

# Mason's Equivalent Circuit Model Rs 1:n Cm Lm Cm Rr Electrical Interconnection (a) BVD Model Acoustic Radiation (a) Impedance Phase

Fig. 2. Lumped-element CMUT equivalent circuit models: (a) Mason's model couples an electrical and a mechanical mesh using a transformer, and accounts for the acoustic radiation and the electrical interconnection using resistances; (b) BVD model represents the electrical impedance of the CMUT; and (c) measured and simulated electrical impedance phase of one of the fabricated CMUTs used in this work, charged at different electric fields.

-80

-85

-90

0

-7.5 MV/cm -8.0 MV/cm

-8.5 MV/cn

4

2

Frequency (MHz)

the wavelength (or, in other words, for frequencies below the Bragg resonance frequency [32]) and if the CMUT aperture is large compared to the wavelength, thus justifying a purely real radiation impedance.

We derived the parameters of Mason's equivalent circuit model from the Butterworth-Van Dyke (BVD) model [33], [34] shown in Fig. 2(b). The BVD model was fit to the water-coupled pre-charged CMUT's electrical impedance measured with an impedance analyzer (Keithley E4990A, Keysight Technologies). We used MATLAB (MathWorks, Natick, MA, USA) to solve the optimization problem, constructing the model by converting the equivalent impedance of the BVD model into the s-domain and representing it with the tf function. We defined the objective function as the sum of the root mean square of the differences between the model and the measured impedance. This includes differences in the impedance when expressed both in the form of magnitude and phase, as well as in the form of real and imaginary parts. To minimize the objective function, we used the *fminsearch* function.

To extract Mason's equivalent circuit parameters from the BVD parameters, the following methodology was employed. First, the specific acoustic impedance of the medium  $(Z_m)$  and the acoustically active area of the transducer (A) were determined. Using these values along with the radiation resistance  $(R_{\rm re})$  from the BVD model, the electromechanical transformation ratio (n) was calculated as  $n = ((Z_m \cdot A)/R_{\rm re})^{1/2}$ . This ratio (n) was then used to transform the BVD mechanical

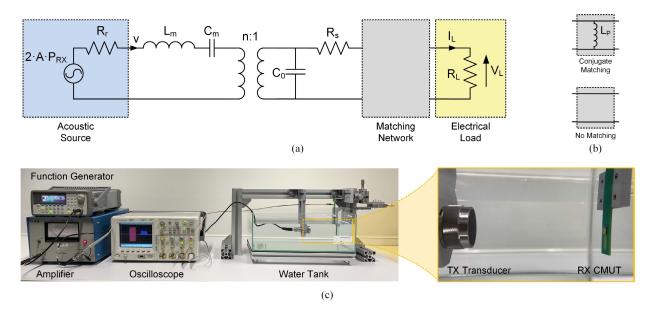


Fig. 3. (a) Equivalent circuit model used for the power transfer simulations. (b) Matching networks analyzed. (c) Experimental setup used for the power transfer experiments.

capacitance ( $C_{\text{me}}$ ), inductance ( $L_{\text{me}}$ ), and resistance ( $R_{\text{re}}$ ) into Mason's parameters. Specifically, the mechanical compliance  $(C_m)$  is computed as  $(C_{\text{me}}/n^2)$ , the mass  $(L_m)$  as  $L_{\text{me}} \cdot n^2$ , and the radiation resistance  $(R_r)$  as  $R_{re} \cdot n^2$ . The blocked capacitance  $(C_0)$  remained unchanged in both models. This systematic transformation allowed the parameters from the BVD model to be effectively translated into Mason's equivalent circuit model, enabling a more comprehensive description of the transducer's behavior when coupled to the propagation medium. We implemented the CMUT Mason's equivalent circuit model in LTSpice (Analog Devices, Norwood, MI, USA). As an example of the methodology effectiveness, we have reported in Fig. 2(c) the phase of the impedance of a prototype CMUT pre-charged at -7.5, -8, and -8.5 MV/cm, and measured and calculated using the LTSpice model, demonstrating a good agreement between the numerical and experimental data. The measured and simulated curves show good agreement in the lower frequency range up to the first peak, where the CMUT vibrates around the fundamental mode. For higher frequencies, the agreement is less accurate as the CMUT vibrates around the second axis-symmetric mode, which the model does not account for. However, the discrepancy remains minor at low charging field values, such as -7.5 MV/cm, and is practically negligible at higher field values within the frequency range of interest.

2) Optimal Load Computation: As mentioned, we analyzed the power transfer from the CMUT to an optimal load with and without using an impedance-matching network. As known, the condition for maximum power transfer from a generator to a load is achieved when the equivalent source impedance, i.e., the Thevenin impedance, and the load impedance are complex conjugates. The impedance of a water-coupled precharged CMUT  $(Z_e)$ , including  $R_s$ , typically consists of a resistance and a capacitive reactance. Therefore, for the case with a matching network, we used a matching inductor  $L_P$ 

and an optimal load resistor  $R_L$  connected in parallel to the CMUT electrical port, dimensioned in such a way as to achieve conjugate matching using the following equations:

$$R_L = \frac{X_e^2 + R_e^2}{R_e} \tag{1}$$

$$R_{L} = \frac{X_{e}^{2} + R_{e}^{2}}{R_{e}}$$

$$L_{P} = -\frac{X_{e}^{2} + R_{e}^{2}}{2\pi f_{m} X_{e}}$$
(1)

where  $R_e$  and  $X_e$  are the real and imaginary parts of  $Z_e$ , respectively, and  $f_m$  is the matching frequency. It should be noted that other matching network configurations are possible, and depending on the application, one can be more suitable than another. Here, the parallel configuration was chosen as there were no specific requirements on the load, such as specific voltage or current ranges, and it was the easiest to implement in this case. However, any chosen matching configuration will include an inductor to compensate for the capacitive reactance of the CMUT introduced by the relatively large blocked capacitance and the relatively low mechanical quality factor in immersion. For the case without matching, we calculated the optimal load as a purely resistive load, for which the maximum power transfer is achieved when the load resistance  $R_L$  is equal to the magnitude of the fluid-coupled CMUT impedance  $|Z_e|$ . A derivation of the maximum power transfer condition for the case without matching is presented in the Appendix.

3) Power Transfer Simulations: We conducted power transfer simulations using the circuit model shown in Fig. 3(a), which is implemented in LTSpice. The model includes an acoustic source connected to the mechanical port of the CMUT Mason's equivalent circuit model, which represents the force exerted on the surface of a CMUT with area A by an impinging pressure wave with amplitude  $P_{RX}$ . A series resistance  $R_s$ , a matching network, and a load resistance  $R_L$  are connected to the CMUT model electrical port. Fig. 3(b) schematically

TABLE I
MASON'S MODEL PARAMETERS

Efield $(MV/cm)$	-7.5	-8.5
$\mathbf{C_0}$ (pF)	547	696
$C_{\mathbf{m}} \text{ (nm/N)}$	5.3	1.9
$\mathbf{L_m}$ ( $\mu H$ )	2.9	1.9
$\mathbf{R_r}$ (g/s)	37	37
$\mathbf{n} \; (\mathrm{mN/V})$	189	316

illustrates the two matching scenarios considered, i.e., Conjugate Matching and No Matching. We chose to model the Si<sub>3</sub>N<sub>4</sub> CMUT with 200-nm B<sub>diel</sub> thickness design variant, charged at two electric field values, -7.5 and -8.5 MV/cm, and analyzed its performance for three values of  $R_s$ : 0, 5, and 10  $\Omega$ . The resistance values were chosen based on the consideration that the series resistance determined from the fitting of the electrical impedance data measured on the fabricated CMUTs is in the order of 10  $\Omega$ . First, we calculated the electrical impedance of the CMUT for the two charging fields and  $R_s = 0 \Omega$ . Then, from their impedance phase curves, we identified the frequencies  $f_L$  and  $f_H$ , which refer to the frequencies at which the phase of the CMUT charged with an electric field of -7.5 and -8.5 MV/cm is, respectively, minimum. For the *Conjugate Matching* case, we calculated the values of  $R_L$  and  $L_P$  for the six combinations of charging field and  $R_s$  at  $f_L$  and  $f_H$ , which function as matching frequency  $f_m$ . For the *No Matching* case, for each charging field variant, we calculated the value of  $R_L$  at their respective minimum phase frequency for the three  $R_s$  values. The CMUT Mason's equivalent circuit model parameters for the two charging field variants are reported in Table I.

For all considered cases, we performed an ac analysis over a frequency range from 100 kHz to 4 MHz, applying an arbitrary pressure  $P_{\rm RX}$  of 1 Pa and calculating the current  $I_L$  and voltage  $V_L$  across the load  $R_L$ . We, then, calculated the received acoustic power as  $W_a = ((A \cdot P_{\rm RX}^2)/(2 \cdot Z_m))$ , where  $Z_m$  is the specific acoustic impedance of the medium, and the electrical power dissipated by the load as  $W_e = (1/2)\Re\{V_L \cdot {\rm conj}(I_L)\}$ , from which we finally derived the power conversion efficiency  $\eta = (W_e/W_a)$  as a function of frequency. In all the simulations, we considered a  $Z_m$  of 1.48 MRayl to model the CMUT operation in water coupling conditions.

4) Power Transfer Experiments: We evaluated the power conversion efficiency of the four pre-charged CMUT variants through ultrasonic power transfer experiments. We used commercial single-element circular immersion transducers (Olympus NDT Inc., Waltham, MA, USA) as TX transducers. We evaluated the performance at 1 and 2.5 MHz, using a 25-mm-diameter TX transducer (Olympus V302S-SU) and a 39-mm-diameter TX transducer (Olympus V395S-SU), respectively. The RX transducers were the pre-charged CMUTs. To determine the optimal distance for maximum power at the RX transducer, we conducted ultrasound field simulations using FOCUS [35]. Based on the simulation results, we performed experiments at 1 MHz with a distance of 110 mm between the TX and RX transducers, and at 2.5 MHz with a distance of 215 mm. Before conducting the power transfer experiment, we measured the pressure field generated by the TX transducer at these distances. This was done by scanning a plane parallel to the surface of the transducer using a needle hydrophone (2762, Precision Acoustics). For the power transfer experiment, both the TX and RX transducers were immersed in a water tank and centrally aligned.

Fig. 3(c) shows the setup used for the power transfer experiments. The driving signal for the TX transducer was generated by a function generator (Agilent 33250A, Agilent Technologies, Santa Clara, CA, USA) and amplified by an RF amplifier (ENI 240L, Electronics and Innovation, Rochester, NY, USA). An oscilloscope (Agilent DSO6034A) was used to measure the input signal to the TX transducer and measure the output voltage from the CMUTs under test. For this experiment, the CMUTs were mounted on a PCB and coated with a thin layer of PBR. We attached the CMUTs PCB to a custom-made 3-D printed holder connected to micromanipulators that allowed the adjustment of the position in the *x*-, *y*-, and *z*-directions.

We conducted the power transfer experiment for each CMUT type and charging electric field. We drove the TX transducers using a 20-cycle sine burst with a pulse repetition frequency of 10 Hz. The acoustic pressure amplitude at the surface of each RX transducer was 114 kPa at 1 MHz and 98.5 kPa at 2.4 MHz, corresponding to an intensity of approximately 420 and 300 mW/cm<sup>2</sup>, respectively. These values were about half of the Food and Drug Administration (FDA) limit of 720 mW/cm<sup>2</sup> for safe use of ultrasound in the human body [36]. We obtained these values from the acoustic characterization of the TX transducers. For each CMUT type and charging electric field, we determined the values of the matching network and optimal load components from the CMUT equivalent impedance, for both the Conjugate Matching and No Matching cases. The matching components consisted of single inductors with a high-quality factor (RF Chokes, BC+/LBC+ Series, EPCOS AG, Munich, Germany) and a precision potentiometer (Bourns, Riverside, CA, USA).

# III. RESULTS AND DISCUSSION

# A. I-V and CV Measurements

Fig. 4(a) shows the results of the I-V measurements in the form of current density-electric field (J-E) curves. Comparing the curves of the Si<sub>3</sub>N<sub>4</sub> samples to the ones of  $Al_2O_3$ , it can be observed that the current density (J) of Si<sub>3</sub>N<sub>4</sub> samples is slightly higher than that of the Al<sub>2</sub>O<sub>3</sub> ones and that the curves exhibit similar trends for devices with the same material, independently of  $B_{\text{diel}}$  thickness. Moreover, the current density is not perfectly symmetric for electric fields of positive and negative polarities, and the breakdown field of  $Si_3N_4$  is slightly higher than the that of  $Al_2O_3$ . Specifically, the Al<sub>2</sub>O<sub>3</sub> samples have a breakdown field around 8–8.5 MV/cm, while the breakdown of Si<sub>3</sub>N<sub>4</sub> samples is between 8.5 and 9.5 MV/cm. Additionally, the two dielectric materials show different J-E curve shapes, with  $Al_2O_3$  showing a gradual rise in current from above 5 MV/cm followed by a narrow region of fast charging above 7.5-8 MV/cm before breakdown, while Si<sub>3</sub>N<sub>4</sub> shows a more gradual increase in current before breakdown. These findings align with the trends observed in

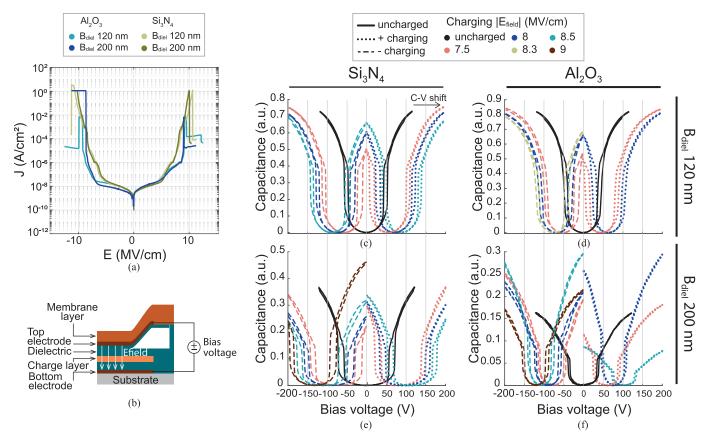


Fig. 4. (a)  $J\!-\!E$  curves of fabricated MIM capacitors with  $Al_2O_3$  and  $Si_3N_4$ . (b) CMUT schematic during charging with positive polarity illustrating the direction of the electric field. (c) and (e) Comparison of CV curve shift for  $Si_3N_4$  samples with  $B_{diel}$  of 120 and 200 nm, respectively, when charged with different electric fields and polarity. (d) and (f) Same as (c) and (e) but for  $Al_2O_3$ .

other research [27], [37] and are due to different transport mechanisms in Si<sub>3</sub>N<sub>4</sub> and Al<sub>2</sub>O<sub>3</sub>. Identifying the exact charge transport mechanisms of electrons is, however, beyond the scope of this work.

Fig. 4(c)-(f) shows the CV curves of the four CMUT variants charged with different electric fields. The CV curve of the pristine devices exhibits symmetry around 0 V. In addition, 0 V coincides with the point of minimum capacitance, indicating that the CMUT is not in a collapsed state and has no charge stored in the dielectric. On the other hand, the pre-charged devices show a shift in the point of minimum capacitance of 60–100 V. The pull-in and snap-out points are beyond 0 V, indicating that the CMUT is in a collapsed state even at 0-V bias, and the presence of charge in the dielectric. Moreover, as expected, the shift is larger for higher charging electric fields due to a larger amount of charge stored in the dielectric. We summarized the shift in collapse voltage due to the charge stored in different CMUT variants in Table II.

Fig. 4 shows that charging the  $Al_2O_3$  devices with  $B_{diel}$  of 120 nm with an electric field exceeding 8 MV/cm was only feasible with negative polarity, as devices charged with positive polarity experienced dielectric breakdown. An analogous behavior can be observed for the  $Si_3N_4$  and  $Al_2O_3$  devices with 200-nm  $B_{diel}$ , as charging with an electric field of 9 MV/cm could only be achieved with an electric field of negative polarity. Slight asymmetries arising from the fabrication process due

TABLE II
SUMMARY OF THE SHIFT IN MINIMUM CAPACITANCE VOLTAGE
EXTRACTED FROM THE CV MEASUREMENTS
Charging Effeld (MV/cm)

			Charging Energ (WV/Chi)					
			-8.5	-8	-7.5	7.5	8	8.5
(mu)	120	Si <sub>3</sub> N <sub>4</sub> Al <sub>2</sub> O <sub>3</sub>	-91.7 -	-77.1 -68.7	-59.9 -53.4	59.8 48.6	74.7 66.7	
$\mathrm{B}_{\mathrm{diel}}$	200	Si <sub>3</sub> N <sub>4</sub> Al <sub>2</sub> O <sub>3</sub>	-114.8 -106.7	-94.8 -90.2	-76.6 -79.8	85.2 58.5	97.1 78.2	116.1 91.4

to the influence of the underlying material on each deposited layer can explain these results and the asymmetries observed in the I-V curves in Fig. 4(a).

Additionally, comparing the CV shift for the two  $B_{\rm diel}$  thicknesses, the 200-nm variants show a larger shift compared to the thinner  $B_{\rm diel}$ , indicating that more charge is stored. Moreover, the effect of the charging electric field polarity is nearly the same for all four variants. An exception is the  ${\rm Si}_3{\rm N}_4$  variant with 200-nm  $B_{\rm diel}$  which shows, although minimal, an opposite trend. However, this could be due to some imprecision in the measurement or inherent variations between samples, and the magnitude of the difference remains small. A larger amount of stored charge implies a higher equivalent built-in bias voltage, with two main consequences: a shift in the device's resonant frequency toward higher values [38] and a longer lifetime, which is discussed in Section III-B.

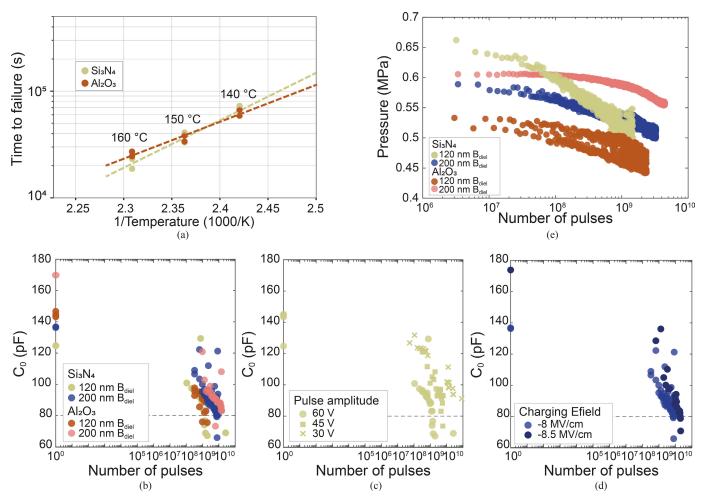


Fig. 5. Accelerated lifetime measurement results. (a) Fitting of the results from the static ALT measurements for the 120-nm  $Al_2O_3$  and  $Si_3N_4$  tested samples. Dynamic charge retention results from impedance monitoring tests. (b) Comparison of electrical capacitance ( $C_0$ ) over the number of stimulus pulses during dynamic ALT for the four tested variants. Results for unipolar stimulus with 60-V amplitude. (c) Effect of unipolar stimulus amplitude on ( $C_0$ ) of 120-nm tetraethylorthosilicate (TEOS)  $Si_3N_4$  samples. (d) Effect of charging electric field on ( $C_0$ ) of 200-nm TEOS  $Si_3N_4$  samples when stimulated with unipolar pulses with 60-V amplitude. (e) Output pressure over the number of stimulus pulses for dynamic ALT with bipolar pulses of 45-V peak-to-peak amplitude for the four CMUT variants.

Ultimately, both the  $Si_3N_4$  variants exhibit a larger shift in the CV curve compared to the  $Al_2O_3$  ones for both polarities. The average trap density of  $Si_3N_4$  is in fact one order of magnitude larger than  $Al_2O_3$  ( $\approx 10^{-3}$  versus  $10^{-4}$  C/m²) [39], [40], [41].

These results confirm that the CMUTs must be charged with electric fields in the region of high current increase [Fig. 4(a)] to achieve a collapse-mode device. This finding is consistent with our observations in previous work [27]. In addition, they suggest that using a thicker  $B_{\rm diel}$  and  ${\rm Si_3N_4}$  as material for the charge storage layer is beneficial in obtaining devices with a larger amount of stored charge. Yet, even more important than the ability to trap charge is the ability to retain it over time and over the device operation.

# B. Accelerated Lifetime Measurements

1) Static: These measurements only provide a general estimation of the charge retention associated with the use of  $Si_3N_4$  or  $Al_2O_3$  in the dielectric stack. Therefore, we only tested the two device variants with  $B_{\rm diel}$  of 120 nm. Fig. 5(a) presents the experimental results, fit to extrapolate the devices' charge

retention at lower temperatures, showing that the predicted charge retention of the Si<sub>3</sub>N<sub>4</sub> variant is longer than for the Al<sub>2</sub>O<sub>3</sub> variant. At the body temperature of 37 °C, the predicted static charge retention is about 7.8 years for the Si<sub>3</sub>N<sub>4</sub> variant and 1.2 years for the Al<sub>2</sub>O<sub>3</sub> variant. However, this charge retention prediction is based on the fitting of an exponential relationship; therefore, small variations in time to failure at high test temperatures will result in large variations in estimated charge retention at lower temperatures such as body or ambient temperature. In addition, at high temperature, the devices' mechanical characteristics can vary significantly, and failure mechanisms other than charge detrapping may also be accelerated compared to as they occur in actual operation conditions. Nevertheless, despite the possibility that these experimental conditions may have degraded the performance of the CMUTs, the results are promising and indicate that the charge is not immediately detrapped.

2) Dynamic: Fig. 5(b) shows the comparison of the performance of the four CMUT variants in terms of the decrease in equivalent electrical capacitance  $C_0$  when subjected to unipolar voltage amplitudes of 60 V. This amplitude is one of the

maximum used in standard CMUTs during transmission. The comparison is based on the number of pulses required for  $C_0$  to reach the threshold value of 80 pF, which corresponds to the capacitance at pull-in. For the samples with 120-nm  $B_{\rm diel}$ , the  $Al_2O_3$  variant requires slightly more pulses to reach this threshold than the  $Si_3N_4$  variant, indicating a longer charge retention. A similar pattern is observed for the samples with a 200-nm  $B_{\rm diel}$  layer, where the  $Al_2O_3$  variant again outperforms the  $Si_3N_4$  variant.

We, then, tested the effect of different unipolar pulse amplitudes on the charge retention of the  $Si_3N_4$  variant with 120-nm  $B_{diel}$ . Fig. 5(c) shows the comparison of the effect of unipolar pulses ranging from 30 to 60 V. As expected, lowering the pulse amplitude significantly increases the charge retention since the electric field generated by the external pulses affects the charge distribution in the CMUT dielectric.

Next, we tested the effect of charging the CMUTs with different electric fields. The CV measurements indicated that higher electric fields during charging lead to more charge being stored in the device. To investigate whether this increased charge storage translates into a longer retention, we compared the charge retention of  $Si_3N_4$  samples with 200-nm  $B_{diel}$  when charged with electric fields of -8 and -8.5 MV/cm. Fig. 5(d) confirms that charging the device with a higher electric field results in a longer charge retention.

Finally, Fig. 5(e) illustrates the decrease in output pressure over the number of stimulation pulses for the four CMUT variants. Considering a threshold of  $10^9$  pulses, a value typically used for the qualification of ultrasound probes produced for point-of-care applications [25], the  $Al_2O_3$  samples with a 200-nm  $B_{diel}$  layer show the best performance with only a 6.6% drop at the threshold of  $10^9$  cycles. The  $Si_3N_4$  samples with a 200-nm  $B_{diel}$  layer showed a decrease in the output pressure of 10%, followed by the devices with the thinner  $B_{diel}$  layer:  $Al_2O_3$  and  $Si_3N_4$  experienced drops of 13.2% and 22.7%, respectively. The significant decrease in output pressure for the  $Si_3N_4$  sample could be attributed to pre-existing degradation in the sample, as the pressure drop is expected to be similar to that of the  $Al_2O_3$  version, considering the results shown in Fig. 5(b).

The results achieved by monitoring the CMUTs' impedance and output pressure show similar trends although a direct comparison between these measurements is challenging. The results here obtained can be used to define the range of applications for which these pre-charged CMUTs can be used. The decrease in electrical capacitance and therefore output pressure over time corresponds to a performance degradation as the CMUT cells gradually snap back to the non-collapsed state. This is advantageous compared to standard externally biased devices, where a short circuit in one cell can abruptly impact the dc bias of other cells, leading to sudden failure of the entire array. Furthermore, charging the devices with a higher electric field does not seem to induce dielectric degradation, as the performance degradation of the devices in Fig. 5(d) follows a similar trend. Moreover, the results from the static charge retention are contradictory to the ones of the dynamic charge retention as, in the former, Si<sub>3</sub>N<sub>4</sub> samples showed longer charge retention prediction compared to Al<sub>2</sub>O<sub>3</sub>.

However, as mentioned earlier, the static charge retention measurements are based on the fitting of an exponential relationship. Therefore, small measurement errors at the high test temperatures could have affected the estimated charge retention at a much lower temperature. Additionally, high temperatures could have elicited different discharge mechanisms in the two different materials.

Overall, these preliminary tests show promising performance. However, additional tests need to be performed to assess the charge retention of the devices. Reliability is a statistical process, so testing a larger number of samples will be necessary to obtain an accurate estimation of their charge retention. Furthermore, the CMUTs were exclusively tested in TX mode. Future tests in RX mode should be conducted to evaluate their charge retention in this mode. This will provide a more comprehensive understanding of their performance across different operational modes.

# C. Power Conversion

1) Power Transfer Simulations: Fig. 6(a) and (b) shows the magnitude and phase of the simulated electrical impedance for the CMUTs charged at -7.5 and -8.5 MV/cm for  $R_s = 0$   $\Omega$ . The magnitude curves indicate that the CMUT charged at -8.5 MV/cm has a generally lower impedance than the one charged at -7.5 MV/cm. This is because it is in a deeper collapse condition, where a larger portion of the CMUT membrane is in contact with the substrate. The phase curves show that the frequency at which the phase is minimum for the CMUT charged at -7.5 MV/cm is  $f_L = 1$  MHz, while for the CMUT charged at -8.5 MV/cm is  $f_H = 2.4$  MHz. This difference is due to the resonance frequency's dependence on the bias condition. The CMUT charged at -8.5 MV/cm has a higher resonance frequency because of the smaller vibrating portion of the CMUT membrane. The respective impedance phase values are substantially the same, approximately  $-76.6^{\circ}$ . Thus, within the conditions analyzed in this article, the charging field of the CMUT mainly affects the magnitude of the electrical impedance and the central operating frequency without significantly altering the electromechanical coupling.

Fig. 6(c) and (d) presents the power conversion simulation results for the Conjugate Matching case with matching frequencies  $f_m$  equal to  $f_L$  (1 MHz) and  $f_H$  (2.4 MHz), respectively, while Fig. 6(e) shows the results for the No Matching case. Each graph shows the efficiency as a function of frequency for the two charging field cases and, for each, the three considered  $R_s$  values. The efficiency curves for the Conjugate Matching case show that maximum efficiency is achieved at  $f_m$  and it reaches 100% for  $R_s = 0 \Omega$ , while it visibly decreases as  $R_s$  increases. Moreover, for each charging field case, the power bandwidth is greater when  $f_m$  is close to the respective frequency at which the phase is minimum. In this condition, for  $R_s = 0 \Omega$ , the fractional power bandwidth at -3 dB is around 52% for both charging field cases. On the other hand, the bandwidth reduces when  $f_m$  is far from the minimum phase frequency. For the No Matching case, the efficiency is highest at the minimum phase frequency, and for  $R_s = 0 \Omega$ , it reaches around 37.5% for both charging field

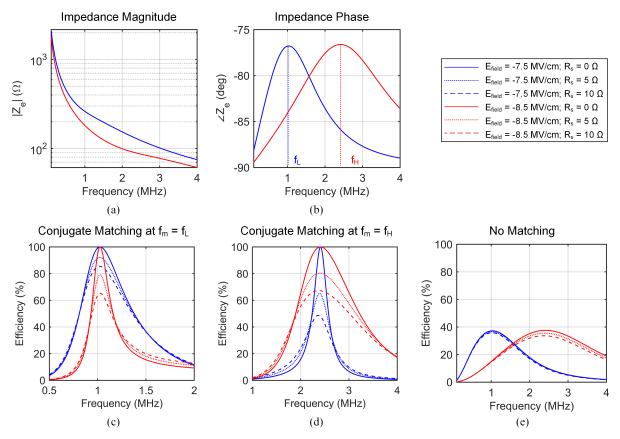


Fig. 6. Simulated electrical impedance (a) magnitude and (b) phase of the two CMUT charging field variants. Simulated power conversion efficiency in the *Conjugate Matching* case for (c)  $f_m = f_L$  and (d)  $f_m = f_H$ , and (e) in the *No matching* case. The blue and red curves are related to charging fields of -7.5 and -8.5 MV/cm, respectively, while the line style is related to different  $R_s$  cases considered.

		Si	3N4 (w22	3)	Al <sub>2</sub> O <sub>3</sub> (w225)		Si <sub>3</sub> N <sub>4</sub> (w218)			Al <sub>2</sub> O <sub>3</sub> (w221)			
	Charging Efield (MV/cm)	-7.5	-8	-8.5	-7.5	-8	-8.5	-7.5	-8	-8.5	-7.5	-8	-8.5
1 MHz	Power Conjugate Matching (mW)	46.1	39.1	39.1	40.5	41.3	41.5	41.4	42.7	33.8	63.1	16.6	19.7
	$\eta$ Conjugate Matching	42.9%	36.4%	36.4%	37.7%	38.4%	38.7%	38.5%	39.7%	31.4%	58.8%	15.5%	18.3%
	Power No Matching (mW)	21	17.9	17.6	16.2	18.9	18.4	18.2	19.2	_	29.3	6.9	7.2
	$\eta$ No Matching	19.5%	16.7%	16.4%	15.1%	17.6%	17.1%	16.7%	17.9%	_	27.3%	6.4%	6.7%
$2.5\mathrm{MHz}$	Power Conjugate Matching $(mW)$ $\eta$ Conjugate Matching Power No Matching $(mW)$ $\eta$ No Matching	20.7 27.2% 10.1 13.2%	28.1 36.9% 16.6 21.8%	62.5 82.0% 39.5 51.9%	21.8 28.4% 8.4 11.0%	24.3 31.9% 12.4 16.2%	46 60.4% 28.8 37.9%	19.9 26.1% 8.7 11.4%	24.6 32.3% 13.2 17.3%	48.8 64.0% 28.6 37.5%	39.6 52.0% 18.4 24.1%	62.1 81.6% 34.2 44.9%	66 86.6% 41.5 54.5%

cases. In this condition, the efficiency decrease as a function of  $R_s$  is less pronounced than in the *Conjugate Matching* case. The fractional power bandwidth at -3 dB is much broader in the *No Matching* case, being 130% and 110% for charging fields of -7.5 and -8.5 MV/cm, respectively.

2) Power Transfer Experiments: We performed the first series of power transfer experiments connecting an optimally matched load consisting of  $L_P$  parallel to  $R_L$  to each of the pre-charged CMUT variants, and we summarized the results obtained in Table III. The results indicate that there is no absolute optimal device variant in terms of power transfer efficiency. Most of the devices charged with electric fields of -7.5 MV/cm have a better performance at 1 MHz compared to 2.4 MHz. On the other hand, devices charged at -8.5 MV/cm have a better performance at 2.4 MHz, reaching efficiencies up to 80%. This is in line with the simulation

results in Fig. 6(c) and (d). We then repeated the previous experiment by connecting a purely resistive load to the CMUT (*No Matching* condition). As for the previous experiments, the results in Table III show no absolute optimal device variant. The charging electric fields for which different devices variants show the highest efficiency at the two test frequencies are the same that exhibited the highest efficiency when connected to the *Conjugate Matching* load. Also, in this case, these results are consistent with the simulation results presented in Fig. 6(e).

A comparison of the simulation and experimental results shows that, despite some variability in the measured efficiency values, there is excellent agreement at high frequency (2.4 MHz) for the -8.5-MV/cm charging field in both the Conjugate Matching and No Matching cases, as well as for the -7.5-MV/cm charging field, especially in the No Matching

Ref.	Material	Topology	Dimensions	Thickness	$\mathbf{f_m}[\mathrm{MHz}]$	$\mathbf{W_e}[\mathrm{mW}]$	η
[42]	PZT	disk	25 mm diameter	-	0.84	62.5	35%
[43]	PZT	disk	$30\mathrm{mm}$ diameter	$2\mathrm{mm}$	1	2.1	20%
[2]	PZT	rectangular	$2 \times 4 \text{ mm}^2$	$2\mathrm{mm}$	1.15	12	2.7%
[3]	PZT	disk	6.8 mm diameter	$0.75\mathrm{mm}$	2.8	-	36.7%
[44]	PZT	disk	$15\mathrm{mm}$ diameter	$3\mathrm{mm}$	0.673	1000	27%
[4]	PZT	disk	$41.36  {\rm mm}^2$	-	1.2	-	50.4%
[5]	PZT	block	$1.7\mathrm{mm}^3$	-	1	0.065	3.4%
[6]	PZT	rectangular	$1 \times 1 \text{ mm}^2$	$1.4\mathrm{mm}$	1.3	0.6	63%
[10]	AIN PMUT	rectangular array	$8 \times 8 \text{ mm}^2$	300 µm	2	0.001	-
[11]	AlN PMUT	disk	$200 \times 200 \; \mu\mathrm{m}^2$		1.7	0.085	0.12%
[12]	AIN PMUT	rectangular array	$2.5\mathrm{mm}^{\dot{2}}$	$7.45\mathrm{\mu m}$	3	0.019	0.236%
[13]	PZT PMUT	rectangular array	$2.058\mathrm{mm}^2$		0.37	0.059	0.375%
[14]	PZT PMUT	rectangular	$2 \times 2 \text{ mm}^2$	$40\mu\mathrm{m}$	0.088	0.7	0.33%
[45]	AlScN PMUT	disk	$12.25\mathrm{mm}^2$	$0.5\mu\mathrm{m}$	0.7	1	8.1%
[26]	Pre-Charged CMUTs	rectangular array	$0.84\times7.56\mathrm{mm^2}$	$700\mu\mathrm{m}$	5.85	0.78	47%
This work	Pre-Charged CMUTs	squared array	$5 \times 5  \mathrm{mm}^2$	700 µm	1 - 2.4	16.6 - 66 $6.9 - 41.5$	15.5% - 86.6% (Conjugate Matching) $6.7% - 54.5%$ (No Matching)

TABLE IV

PERFORMANCE SUMMARY OF THE ULTRASONIC RECEIVER AND COMPARISON WITH THE STATE OF THE ART

case. However, at low frequency (1 MHz), the agreement between the simulations and experiments is less consistent for both charging fields, particularly in the *Conjugate Matching* case, where the measured efficiency is significantly lower than the simulated one. This discrepancy at low frequency can be attributed to the relatively high inductance values used, which are approximately an order of magnitude higher than those used for high-frequency matching. At these higher inductance values, the performance of commercial inductors is more affected by nonidealities and parasitic effects (e.g., lower self-resonance, higher equivalent series resistance (ESR), etc.). Moreover, during some experiments, we connected multiple inductors in series to achieve the correct inductance values, which may have further increased parasitic effects due to their interconnection.

Table IV shows the comparison of the results achieved in this work to the performance reported by other groups using PZT transducers and MUTs. The efficiency is calculated considering the total active receiver area, i.e., including the space between the active transducer elements. Our experiments yielded power conversion efficiencies within the range of, and often superior to, those obtained with PZT transducers, and significantly higher than those achieved with PMUTs. Even the lowest efficiency values from our experiments significantly exceeded those achieved with PMUTs. These lower values can be attributed to nonidealities in the components and experimental setup that are not taken into account in the model, as previously discussed. Additionally, our experiments demonstrated that even without using a matching inductor, we achieved efficiencies comparable to the values reported in Table IV. These results are significantly given the challenges associated with using an inductor in an IMD or integrating a CMUT onto an ASIC.

In general, it is advantageous to operate at the frequency at which the phase is minimum, whether a matching network is used or not. When using matching networks, where ideally the CMUT reactance can be completely compensated around a selected frequency, operating at the minimum phase frequency provides the maximum power bandwidth and consequently greater tolerance to variability of any of the parameters. In the absence of a matching network, it is also convenient to operate at the minimum phase frequency, as it corresponds to the condition of the lowest reactance-to-resistance ratio, resulting in maximum power transfer to an optimal load and thus maximum efficiency. In addition, when using a matching network, it is beneficial if the series resistance of the electrical interconnections is small compared to the CMUT's real part of the impedance and to use inductors with low ESR.  $R_s$ , in fact, limits the current flowing from the inductor toward the equivalent capacitive reactance, decreasing its efficiency in compensating the capacitive part. In addition, the matching inductor itself is not an ideal component having its own parasitic series resistance. Finally, the interconnection's series resistance as well as the inductor's ESR may significantly affect the efficiency to such an extent that beyond certain values, it is preferable to operate without matching networks.

Varying the built-in bias voltage by charging the devices at different electric fields allows shifting the frequency at which their phase is minimum to higher or lower values. However, it does not impact the minimum phase value [Fig. 6(b)]. For higher charging fields, the impedance magnitude is lower, resulting in better matching to low impedance loads, which can be advantageous depending on the load voltage and current requirements. However, it must be considered that the ratio between the real part of the impedance and the series resistance becomes less favorable, causing a decrease in efficiency. Another advantage of lowering the impedance magnitude is that smaller inductance values and thus also physically smaller inductors are needed for matching, which can be relevant if space constraints exist. Moreover, higher charging fields allow for greater dynamic ranges, as the CMUT is biased in deeper collapse, farthest from the snapback condition, thus allowing higher RX pressure operation. On the other hand, choosing a higher charging field, and therefore a higher minimum phase frequency, must be done with the consideration of the application and the propagation medium.

The latter determines the power loss between the transmitter and receiver. For example, within the body at a distance of 10 cm between the transmitter and receiver, using an operating frequency of 2.4 MHz results in 0.9 dB more attenuation at the receiver compared to 1 MHz. Therefore, in such cases, selecting a lower frequency might be advantageous despite the need for a larger matching inductor.

Finally, given that in these experiments we used about half of the maximum allowed ultrasound intensity for safe in-body use [36], the power at the load is in the range of values required by IMDs. Although, in these experiments, we considered simplified scenarios in terms of the type of matching circuit, choosing a matching type that satisfies the current and voltage requirements of a real application load is not expected to significantly change the performance.

Ultimately, since the performance of different device variants is comparable when connected to an optimally matched load, future optimization efforts will focus on improving charge retention over time, although for certain applications, such as disposable devices used in short-term or acute settings, the existing charge retention levels are already sufficient. As previously discussed, Si<sub>3</sub>N<sub>4</sub> has a higher charge-trapping capacity compared to Al<sub>2</sub>O<sub>3</sub>, yet their overall charge retention performance is similar, with minimal differences observed between the two materials. However, from a manufacturing perspective, Si<sub>3</sub>N<sub>4</sub> has notable advantages. Its deposition is achieved using PECVD, which is significantly faster than the ALD process required for Al<sub>2</sub>O<sub>3</sub>. This faster deposition process makes Si<sub>3</sub>N<sub>4</sub> a more suitable choice for high-volume production. Additionally, the transport mechanism in Si<sub>3</sub>N<sub>4</sub> is charge-based and well-documented in the literature, providing a solid foundation for further optimization.

# IV. CONCLUSION

In this article, we investigated the performance of pre-charged collapse-mode CMUTs as ultrasonic receivers in wireless power transfer for IMDs. We presented a lowtemperature, sacrificial release-based microfabrication technology for collapse-mode CMUTs that was modified to introduce a charge-storage dielectric layer to provide a built-in bias, thereby eliminating the need for an external high-voltage generator. We fabricated CMUT prototypes using two different charge storage materials, specifically PECVD Si<sub>3</sub>N<sub>4</sub> and ALD Al<sub>2</sub>O<sub>3</sub>, and investigated the effect of the dielectric thickness separating them from the conductive electrode. The fabricated prototypes were pre-charged at different electric fields and characterized by I-V and CV measurements to evaluate the effective bias point. Their charge retention was assessed through electrical stress tests supported by electrical impedance measurements. We, then, analyzed the performance of the realized prototypes using both simulations and measurements to evaluate the power conversion efficiency to an optimal load as a function of bias condition and operating frequency, with or without electrical matching. Simulations, based on accurate equivalent circuit modeling with parameters fit from impedance measurements, allowed us to analyze the effect of parasitic series resistance on efficiency and to interpret the experimental power conversion results. We observed

and discussed how the highest efficiencies can be obtained under CMUT precharging with the highest electric fields and at higher frequencies, and highlighted the extent to which the effect of series resistance can limit the efficiency. The measurements showed efficiencies up to 54.5% and 86.6% under no matching and conjugate matching conditions, respectively. The achieved efficiencies are significantly higher than other MUTs reported in the literature and comparable or superior to those obtained with state-of-the-art conventional bulk piezoelectric transducers.

The results of this article demonstrate that pre-charged collapse-mode CMUT is a promising technology for high-performance, integrated, lead-free transducers suitable for IMDs and systems. This technology is also promising for applications where the need for externally supplied high bias voltages is a critical limiting factor, such as ultraportable ultrasound imaging systems, wearable devices and patches, intravascular or intracardiac ultrasound catheters, or even for neuromodulation, thanks to the design freedom and modularity of this CMUT platform.

## **APPENDIX**

To determine the optimal load in the case without matching, we derived the maximum power transfer condition for a generator with a complex equivalent source impedance and a purely resistive load. Consider a voltage generator  $V_e$  with an equivalent series source impedance  $Z_e = R_e + j X_e$ . When the load  $Z_L$  is purely resistive,  $Z_L = R_L$ , the power transferred to the load is expressed as

$$P_{L} = |I_{L}|^{2} \cdot R_{L}$$

$$= \frac{|V_{e}|^{2}}{|Z_{e} + R_{L}|^{2}} \cdot R_{L}$$

$$= \left| \frac{V_{e}}{(R_{e} + R_{L}) + jX_{e}} \right|^{2} \cdot R_{L}$$

$$= \frac{|V_{e}|^{2} \cdot R_{L}}{(R_{e} + R_{L})^{2} + X_{e}^{2}}$$
(3)

where  $I_L$  is the current through the load resistor  $R_L$ . To maximize  $P_L$ , we differentiate  $P_L$  with respect to  $R_L$  and set the derivative equal to zero

$$\frac{dP_L}{dR_L} = \frac{|V_e|^2 \left[ (R_e + R_L)^2 + X_e^2 - 2R_L(R_e + R_L) \right]}{\left[ (R_e + R_L)^2 + X_e^2 \right]^2} = 0.$$
 (4)

Simplifying this equation gives

$$(R_e + R_L)^2 + X_e^2 - 2R_L(R_e + R_L) = 0 (5)$$

which reduces to

$$R_L^2 = R_e^2 + X_e^2. (6)$$

Therefore,

$$R_L = \sqrt{R_e^2 + X_e^2} = |Z_e|. (7)$$

This result shows that the value of  $R_L$  that maximizes the power transferred to the load is indeed the magnitude of the source impedance,  $|Z_e|$ .

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Marta Saccher is with the Department of Microelectronics, Faculty of Electrical Engineering, Mathematics and Computer Science, Delft University of Technology, 2628 CD Delft, The Netherlands (e-mail: m.saccher@tudelft.nl).

Alessandro Stuart Savoia is with the Department of Industrial, Electronic, and Mechanical Engineering, Roma Tre University, 00146 Rome, Italy (e-mail: alessandro.savoia@uniroma3.it).

Rob van Schaijk and Johan H. Klootwijk are with the MEMS and Micro Devices Department, Philips Engineering Solutions, 5656 AE Eindhoven, The Netherlands.

Ronald Dekker is with the Department of Microelectronics, Faculty of Electrical Engineering, Mathematics and Computer Science, Delft University of Technology, 2628 CD Delft, The Netherlands, and also with the MEMS and Micro Devices Department, Philips Engineering Solutions, 5656 AE Eindhoven, The Netherlands.

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Marta Saccher (Member, IEEE) received the B.Sc. degree in biomedical engineering from the Polytechnic University of Milan, Milan, Italy, in 2017, and the M.Sc. degree (cum laude) in biomedical engineering and the Ph.D. degree (cum laude) in MEMS ultrasound from Delft University of Technology (TU Delft), Delft, The Netherlands, in 2019 and 2024, respectively.

During her Ph.D., she was a Guest Researcher with Philips, Eindhoven, The Netherlands. She is currently holding a scientist

position at TNO, The Hague, The Netherlands, working on ultrasound for different applications.



Alessandro Stuart Savoia (Member, IEEE) received the Laurea (M.S.) and Ph.D. degrees in electronic engineering from Roma Tre University, Rome, Italy, in 2003 and 2007, respectively, and the National Scientific Qualification (ASN) for Full Professor in electronics, in 2020.

Since 2007, he has been holding a postdoctoral research position at the Department of Electronics Engineering, Roma Tre University. From 2008 to 2010, he participated, as a Co-Founder and a Research and Development

Manager, in an academic spin-off company of Roma Tre University, focused on the industrial exploitation of MEMS-based ultrasonic transducers [capacitive micromachined ultrasonic transducer (CMUT)], leveraging scientific results achieved during his Ph.D. and postdoctoral research. In 2014, he became an Assistant Professor of electronics with the Department of Engineering, Roma Tre University. He leads research activities with the Acousto-Electronics Laboratory, Department of Industrial, Electronic, and Mechanical Engineering, Roma Tre University, in the field of ultrasonic transducers. He has authored or co-authored more than 120 articles in international journals and conferences, most of them published in IEEE TRANSACTIONS and IEEE Conference Proceedings, and five book chapters. He holds seven international patents. His research interests are mainly focused on the development and system integration of MEMS ultrasonic transducers [CMUT and piezoelectric MUT (PMUT)].

Dr. Savoia serves the IEEE UFFC Society as an Associate Editor for IEEE TRANSACTIONS ON ULTRASONICS, FERROELECTRICS, AND FREQUENCY CONTROL, a Guest Editor for IEEE OPEN JOURNAL OF ULTRASONICS, FERROELECTRICS, AND FREQUENCY CONTROL, the Chair for the TPC Group 5 "Transducers and Transducer Materials" of the International Ultrasonics Symposium, and an Elected Member for AdCom.



Rob van Schaijk was born in Schaijk, The Netherlands, in 1971. He received the master's degree in applied physics from the Technical University of Eindhoven, Eindhoven, The Netherlands, in 1995, and the Ph.D. degree in semiconductor physics from the University of Amsterdam, Amsterdam, The Netherlands, in 1999.

He has 20 years of experience in semiconductors, MEMS, and IC technology in different positions, from Senior Scientist to Research

and Development Manager. From 1999 to 2007, he worked with Philips Research, Philips Semiconductors, Eindhoven, and NXP Semiconductors, Eindhoven, on topics around silicon processing. From 2007 to 2017, he worked as a Principal Researcher, a Program Manager, and a Research and Development Manager with the Holst Centre, IMEC, Leuven, Belgium, with a focus on the development of energy harvesters and sensors for use in wireless sensor nodes. In 2017, he joined the MEMS and Micro Devices Department, Philips Innovation Services, Eindhoven, as a Principal Architect. His main responsibility is MEMS process development with Philips MEMS Foundry, Eindhoven, with a focus on capacitive micromachined ultrasonic transducer (CMUT) technology. He has authored or co-authored over 100 publications and conference contributions, and holds more than 35 patents.



Johan H. Klootwijk (Senior Member, IEEE) received the M.Sc. and Ph.D. degrees in electrical engineering from the University of Twente, Enschede, The Netherlands, in 1993 and 1997, respectively.

He then joined the Philips Research Laboratories, Eindhoven, The Netherlands, where he has worked on a wide range of topics, a.o. wideband RF applications (a.o. Si, SiGe, and InP bipolar technologies), gas sensors, thin extreme ultraviolet lithography (EUV) membranes (pellicles)

for the next-generation lithography tools, and wearable MEMS-based ultrasound patches. Since 1999, he has been a Senior Lecturer of semiconductor devices with the CTT Institute, Eindhoven, and the T2Prof Institute, Eindhoven. In 2021, he was appointed as Team Lead of the Ultra-Sound Applications Team, Philips Research, Eindhoven, working on digital ultrasound (US) solutions. In 2023, he moved to the Philips MEMS Foundry, Eindhoven, after the closure of Philips Research. In 2024, he was promoted to the grade of Principal Scientist. He has authored or co-authored over 80 scientific publications and conference contributions, and holds more than 25 U.S. patents.

Dr. Klootwijk received the Best Paper Award for his contribution to the ESSDERC Conference in 2001 and the Best Poster Award on the NATO-ASI Summercourse on ALD in 1995. For part of his work, he received the Bronze Award for the NXP Invention of the Year 2007 and the Bronze and Silver Invention Awards in 2015 and 2020, respectively. He served as the Tutorial Chairperson for the International Conference on Measurement and Teststructures (ICMTS) in 2002, 2008, 2011, and 2024, and the Technical Chairperson in 2014. As of 2025, the MEMS Foundry is continue as an independent company, named XIVER.



Ronald Dekker received the M.Sc. degree in electrical engineering from the Technical University of Eindhoven, Eindhoven, The Netherlands, and the Ph.D. degree from the Technical University of Delft, Delft, The Netherlands.

In 1988, he joined Philips Research, Eindhoven, where he worked on the development of RF technologies for mobile communication. Since 2000, his focus shifted to the integration of complex electronic sensor functionality on the tip of the smallest minimal invasive instruments

such as catheters and guide wires. In 2007, he was appointed as part-time Professor with the Technical University of Delft, with a focus on organ-on-chip and bioelectronics medicines. Since 2013, he has been an initiator of a number of large European initiatives that all have in common the development of open technology platforms for electronic medical devices. He published in leading journals and conferences and holds more than 70 patents.